



A LIMITED LIABILITY COMPANY

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KLA SPECTRA FX 100 FILM THICKNESS MEASUREMENT TOOL

SN 0307801
Vintage 2003
200 and 300 mm wafer capable

Wafer stage: Vacuum adsorption
Stage resolution : X, Y 0.1 μ m
: Z (1x) 0.1 μ m
: Z (4x,15x) 0.005 μ m
Stage stopping accuracy 3: \pm 1.5 μ m
Wafer size : 100 - 200mm (200DO/SS/DS) or 200 - 300mm (300SO/DF)
Automatic focusing mechanism: Piezo drive (only 4x,15xDBS, SE and SWE): Linear drive (only 1xDBS)
Largest range of vision: 1.125mmx1.50mm (at the time of 1x objective use)

Illuminant

- Xenon arc lamp (220~780nm)
- D2 lamp (190nm~) (Option function)
- The HeNe laser (option function) for SWE

Film thickness total of each stratum 20.0nm-5 μ m
Reflectance ratio measurement
Measurement wave length: 220
Optional wave length 190nm to 780nm

SE Option and SWE option

Pattern recognition system

- CCD camera
- COGNEX 8100+PatMax system:
Standard



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